

## 2009 — SETSUHARA Yuichi

### Scientific Papers/Commentary Articles

1. Y. Setsuhara, K. Takenaka, K. Cho, J.G. Han, Large-Area and Low-Damage Processes for Hybrid Flexible Device Fabrications with Reactive High-Density Plasmas Driven by Multiple Low-Inductance Antenna Modules, *Journal of Physics: Conference Series*, 165, 12042-1-12042-6, 2009
2. Y. Setsuhara, K. Cho, K. Takenaka, M. Shiratani, M. Sekine, M. Hori, E. Ikenaga, S. Zaima, Low-Damage Surface Modification of Polymethylmethacrylate with Argon-Oxygen Mixture Plasmas Driven by Multiple Low-inductance Antenna Units, *Thin Solid Films*, 518, 3561-3565, 2010
3. Y. Setsuhara, K. Nagao, M. Shiratani, M. Sekine, M. Hori, Development of density-inclination plasmas for analysis of plasma nano-processes via combinatorial method, *Thin Solid Films*, 518, 1020-1023, 2009
4. Y. Setsuhara, K. Cho, K. Takenaka, A. Ebe, M. Shiratani, M. Sekine, M. Hori, E. Ikeitaga, H. Kondo, O. Nakatsuka and S. Zaima, Plasma Surface Treatment of Polymers with Inductivity Coupled RF Plasmas Driven by Low inductance Antenna Units, *Thin Solid Films*, 518, 1006-1011, 2009
5. Y. Setsuhara, K. Cho, M. Shiratani, M. Sekine and M., Hori, E. Ikeitaga and S. Zaima, X-Ray Photoelectron Spectroscopy for Analysis of Plasma-Polymer Interactions in Ar Plasmas Sustained via RF Inductive-Coupling with Low-Inductance Antenna Units, *Thin Solid Films*, 518, 3555-3560, 2010
6. Tae Joon Byun , Sung Il Kim, Youn Joon Kim, Yoon Suk Choi, In Sik Choi, Yuichi Setsuhara, and Jeon Geon Han, Surface Modification of Polyimide for Improving Adhesion Strength by Inductively Coupled Plasma, *Japanese Journal of Applied Physics*, 48, 08HL01-1- 08HL01-4, 2009
7. Tae J. BYUN, Kyung S. SHIN, Youn J. KIM, Jeon G. HAN and Y. Setsuhara, Polycarbonate Surface Treatment by Using an Inductively-Coupled Plasma, *Journal of the Korean Physical Society*, Vol. 55, No. 5, 1785 1789, 2009
8. K. Takenaka, Y. Setsuhara, K. Nishisaka A. Ebe, Radial Profile Control of Cylindrical Plasma Source with Multiple Low-Inductance Antenna Units, *Plasma Processes and Polymers*, 6, S278-S281, 2009